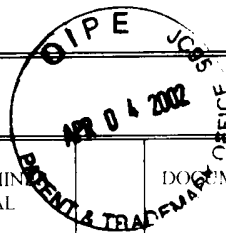


Form PTO-1449 (Modified)  <b>LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT</b> (Use several sheets if necessary)	Atty Docket No.: G0131	Serial No.: 10/050,417
	Applicant: Khoi A. Phan, et al.	
	Filing Date: 1/16/2002	Group: Unknown



REFERENCE DESIGNATION U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA		COPY OF PAPERS ORIGINALLY FILED			
	AB					
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OTHER ART(Including Author, Title, Date, Pertinent Pages, etc.)

JRC	AI	"Understanding the DUV Resist Development Process Using A Develop Residue Monitoring Technique". C. Pike and J. Erhardt. Presented at Interface 1999: Microlithography Symposium, November 14-16, 1999.
JRC	AM	"An Investigation of Circular Resist Residue Defects in the Development of a 0.16µm Flash Process". J. Erhardt, K. Phan, and J. Cheng.
EXAMINER <i>J. K. [signature]</i>		DATE CONSIDERED <i>6/19/03</i>

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.